Appln. No.: 10/044,261

Amendment Dated June 25, 2004

Reply to Restriction Requirement of June 15, 2004

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Original) A method for forming a multi-layer positive-working imageable element, the imageable element comprising:

a substrate comprising a hydrophilic surface;

an underlayer over the hydrophilic surface of the substrate; and

an imageable layer over the underlayer;

the method comprising the steps of:

- (a) coating an underlayer over a hydrophilic surface of a substrate;
- (b) coating an imageable layer over the underlayer; and
- (c) heating the imageable element at a temperature between about 130°C and about 200°C for a time sufficient to increase resistance of the imageable element to an alkaline developer and to decrease the white light sensitivity of the imageable element;

in which:

the imageable element comprises a photothermal conversion material;

the imageable layer is ink receptive;

the imageable layer is insoluble in the alkaline developer;

the imageable layer comprises:

a first polymeric material, and

an o-diazonaphthoquinone containing material; and

the underlayer comprises a second polymeric material.

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2. (Original) The method of claim 1 in which the imageable element is heated to a temperature between about 130°C and about 200°C for about 30 seconds to about 10 minutes.

- 3. (Original) The method of claim 1 in which the second polymeric material is selected from the group consisting of (1) copolymers that comprise a carboxylic acid, an N-substituted cyclic imide, and an amide functional group; (2) copolymers that comprise a pendent urea group; and (3) copolymers that comprise a pendent sulfonamide group.
- 4. (Original) The method of claim 1 in which the *o*-diazonaphthoquinone containing material is either a compound that comprises an *o*-diazonaphthoquinone moiety attached to a ballasting moiety that has a molecular weight of at least 1500 but less than about 5000, or a novolac resin derivatized with an *o*-diazonaphthoquinone moiety.
- 5. (Original) The method of claim 4 in which the first polymeric material is either a novolac resin or a novolac resin derivatized with an o-diazonaphthoquinone moiety.
- 6. (Original) The method of claim 5 in which second polymeric material is selected from the group consisting of (1) copolymers that comprise a carboxylic acid, an N-substituted cyclic imide, and an amide functional group; (2) copolymers that comprise a pendent urea group; and (3) copolymers that comprise a pendent sulfonamide group.
- 7. (Original) The method of claim 6 in which the imageable element is heated to a temperature between about 130°C and about 200°C for about 30 seconds to about 10 minutes.
- 8. (Original) The method of claim 1 in which the first polymeric material is either a novolac resin or a novolac resin derivatized with an *o*-diazonaphthoquinone moiety.
- 9. (Original) The method of claim 8 in which the second polymeric material is a copolymer that comprises about 25 to about 75 mol% of N-phenylmaleimide; about 10 to about 50 mol% of methacrylamide; and about 5 to about 30 mol% of methacrylic acid.
- 10. (Original) The method of claim 9 in which the second polymeric material comprises about 35 to about 60 mol% of the N-phenylmaleimide; about 15 to about 40 mol% of the methacrylamide; and about 10 to about 30 mol% of the methacrylic acid.
- 11. (Original) The method of claim 8 in which the second polymeric material comprises about 20 to 80 wt% of one of more monomers represented by the general formula:

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$$CH_2=C(R)-CO_2-X-NH-CO-NH-Y-Z$$
,

in which R is -H or -CH<sub>3</sub>; X is a bivalent linking group; Y is a substituted or unsubstituted bivalent aromatic group; and Z is -OH, -COOH, or -SO<sub>2</sub>NH<sub>2</sub>.

- 12. (Original) The method of claim 11 in which R is  $CH_3$ ; X is -( $CH_2CH_2$ )-; Y is unsubstituted 1,4-phenylene; and Z is -OH.
- 13. (Original) The method of claim 8 in which the second polymeric material comprises (1) about 10 to 90 mol% of a sulfonamide containing monomer unit; (2) acrylonitrile or methacrylonitrile; and (3) methyl methacrylate or methyl acrylate.
- 14. (Original) The method of claim 8 in which the imageable element is heated to a temperature between about 130°C and about 200°C for about 30 seconds to about 10 minutes.
- 15. (Original) The method of claim 1 in which the first polymeric material is a novolac resin and the *o*-diazonaphthoquinone containing material is novolac resin derivatized with an *o*-diazonaphthoquinone moiety.
- 16. (Original) The method of claim 1 in which the second polymeric material is a copolymer that comprises about 25 to about 75 mol% of N-phenylmaleimide; about 10 to about 50 mol% of methacrylamide; and about 5 to about 30 mol% of methacrylic acid.
- 17. (Original) The method of claim 1 in which the first polymeric material is novolac resin and the *o*-diazonaphthoquinone containing material is a compound that comprises an *o*-diazonaphthoquinone moiety attached to a ballasting moiety that has a molecular weight of at least 1500 but less than about 5000.
- 18. (Original) The method of claim 1 in which the second polymeric material is a copolymer that comprises about 25 to about 75 mol% of N-phenylmaleimide; about 10 to about 50 mol% of methacrylamide; and about 5 to about 30 mol% of methacrylic acid.
- 19. (Original) A multi-layer positive-working imageable element, the element comprising a substrate comprising a hydrophilic surface; an underlayer over the hydrophilic surface of the substrate; and an imageable layer over the underlayer;

the element prepared by a method comprising the steps of:

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- (a) coating an underlayer over a hydrophilic surface of a substrate;
- (b) coating an imageable layer over the underlayer; and
- (c) heating the imageable element at a temperature between about 130°C and about 200°C for a time sufficient to increase resistance of the imageable element to an alkaline developer and to decrease the white light sensitivity of the imageable element;

in which:

the imageable element comprises a photothermal conversion material;

the imageable layer is ink receptive;

the imageable layer is insoluble in the alkaline developer;

the imageable layer comprises:

a first polymeric material, and

an o-diazonaphthoquinone containing material; and

the underlayer comprises a second polymeric material.

- 20. (Original) The element of claim 19 in which the imageable element is heated to a temperature between about 130°C and about 200°C for about 30 seconds to about 10 minutes.
  - 21. and 22. Cancelled